

A proven PECVD platform from Oxford Instruments, designed for advanced thinfilm deposition processes and research applications.



KEY FEATURES

- ▶ Used Oxford Instruments Plasmalab System 100 PECVD platform
- ▶ Configured for 200 mm wafer processing
- ▶ Designed for plasma enhanced chemical vapor deposition applications
- ▶ Clean industrial cabinet and integrated process module layout
- ▶ Ideal for R&D, pilot line, or specialty thin-film process environments